
Fabrication of EUV light source with cold cathode electron beam (C-beam)

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Why C-beam for EUV lighting?

01

Instantaneous operation

02

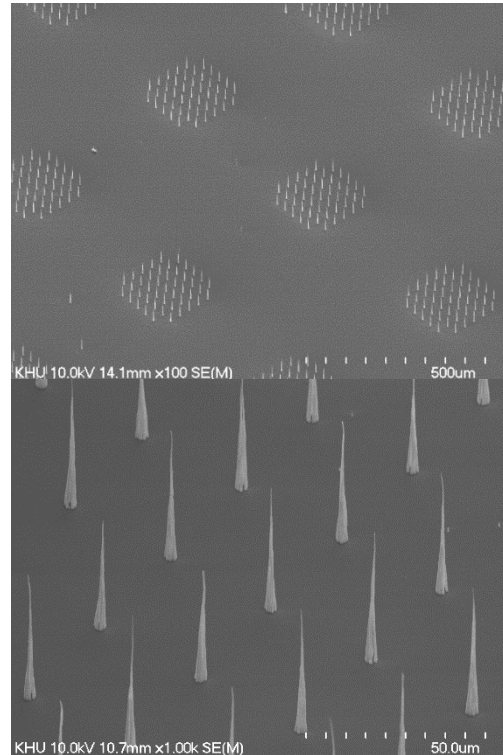
High output power

03

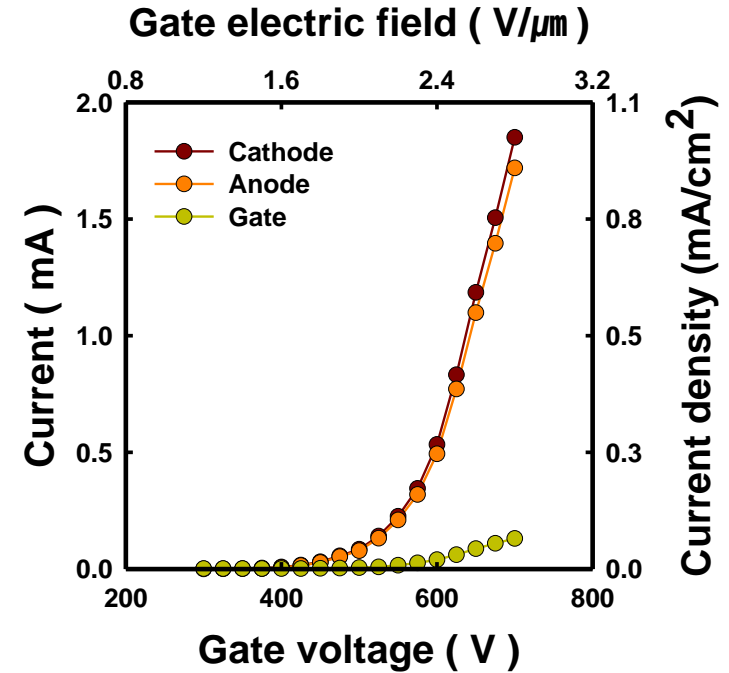
Large area

04

Eco-friendly



[SEM image of CNTs]

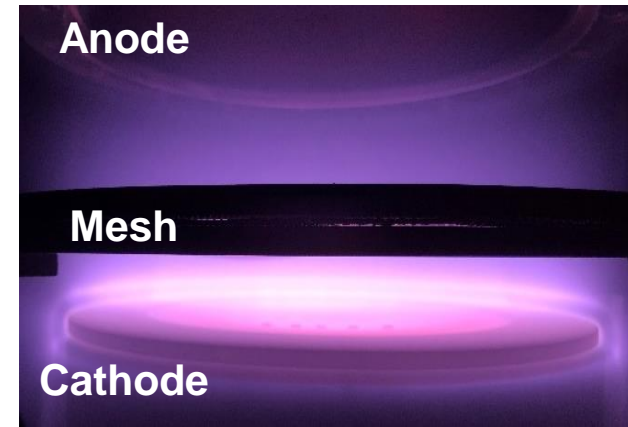
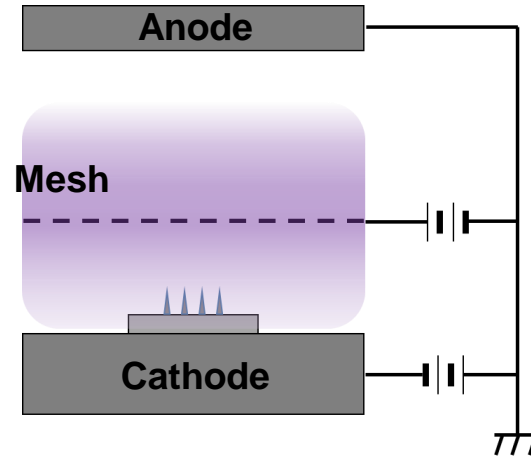
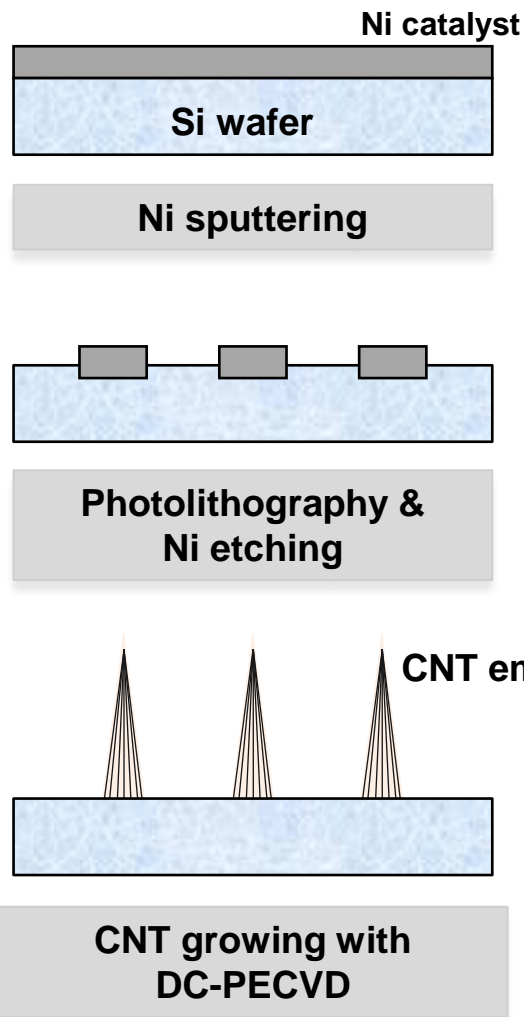


[I-V characteristics of C-beam]

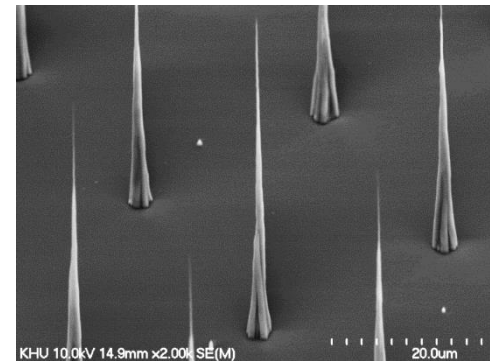
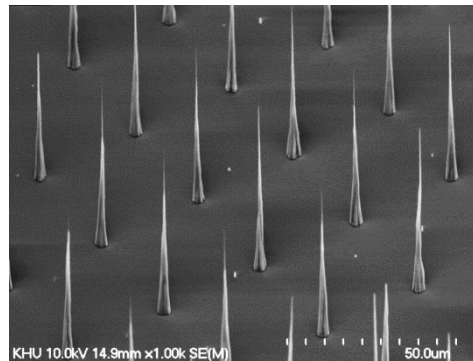
The SEM image & I-V characteristics of C-beam

- Carbon nanotube (CNT)-based cold cathode electron beam (C-beam) was manufactured for EUV lighting.

Fabrication process of the CNT emitters



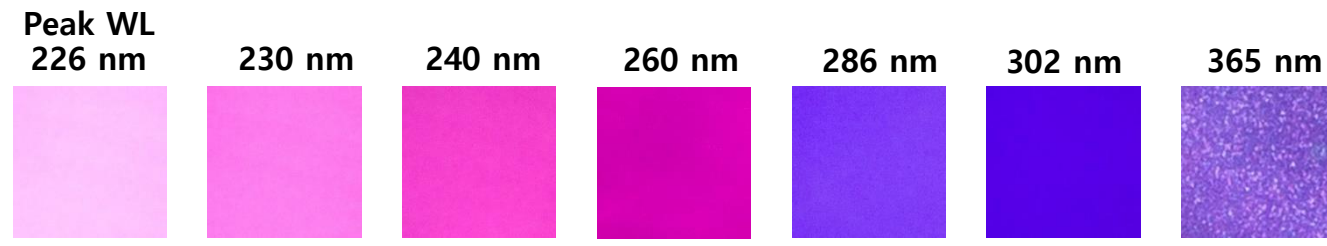
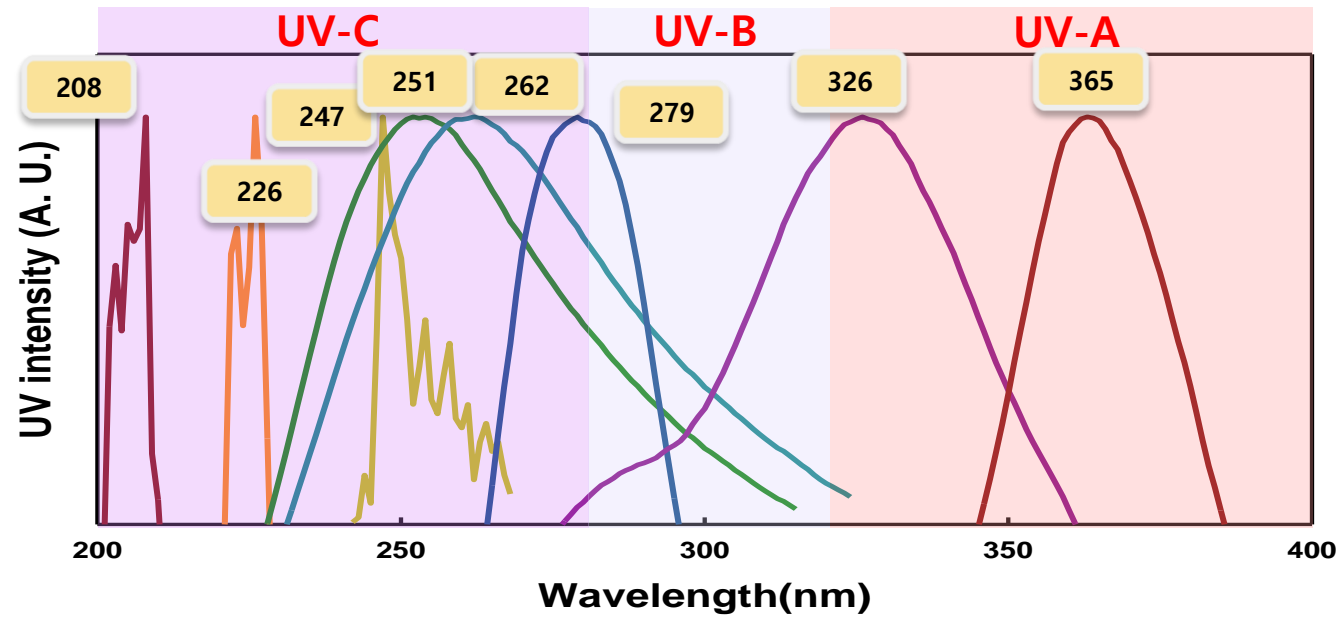
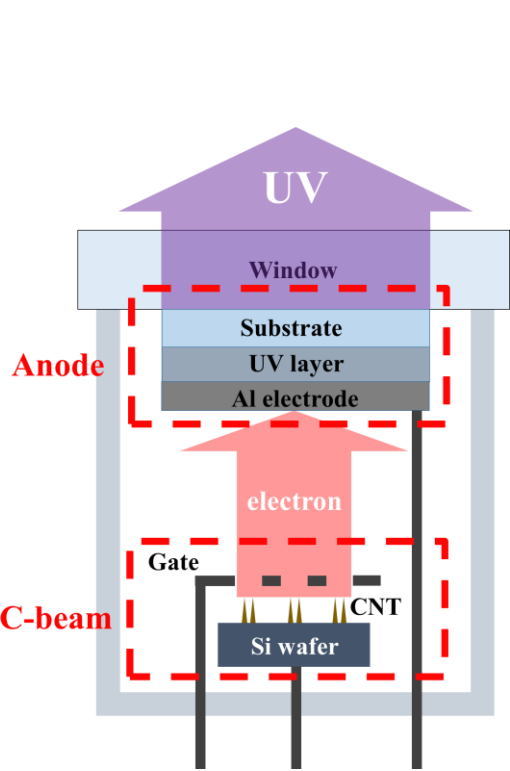
Triode DC-PECVD system



Vertically aligned CNT emitters

- The CNT emitters have fully vertically aligned structure and grown pre-defined selective area.

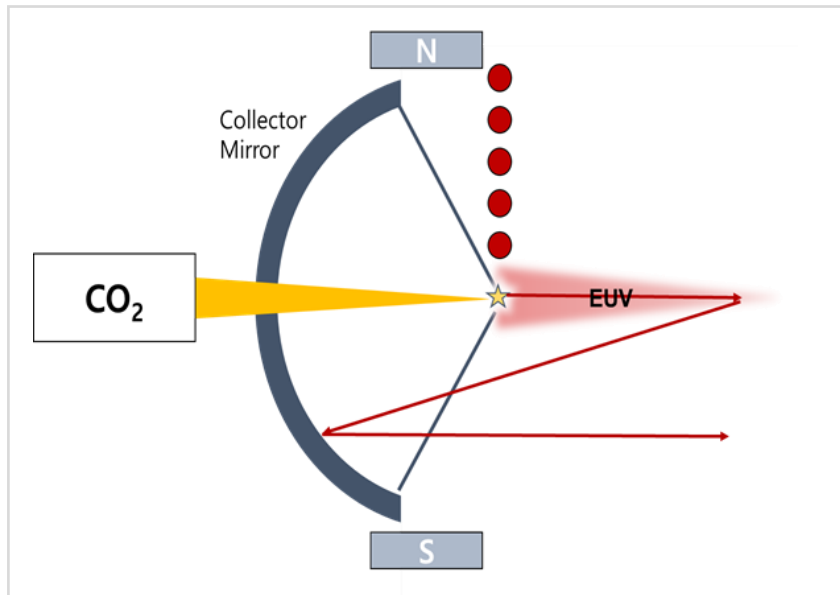
UV Light developed at Kyung Hee University (UV-A to UV-C)



UV spectrum & captured image of UV light generation using C-beam

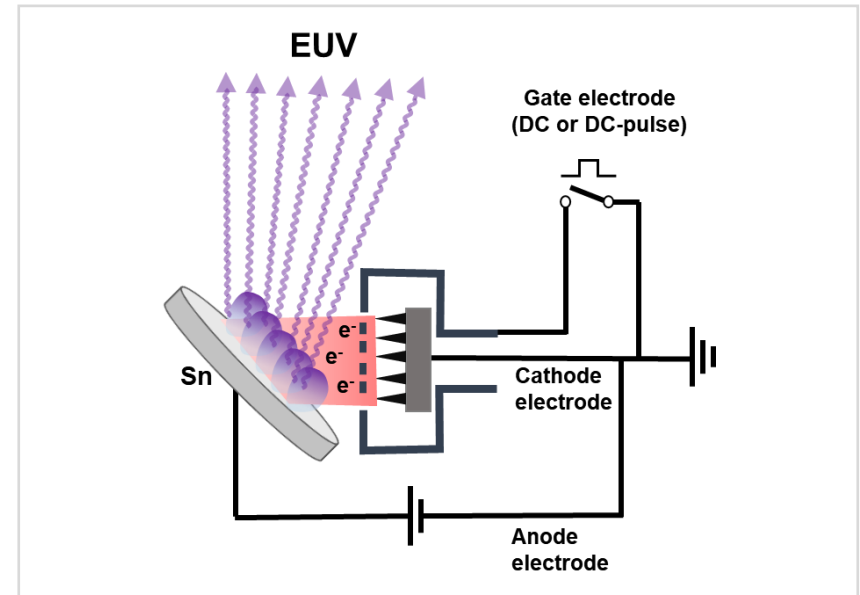
- UV generation was confirmed with C-beam pumping technology.

Comparison btw LPP and C-beam



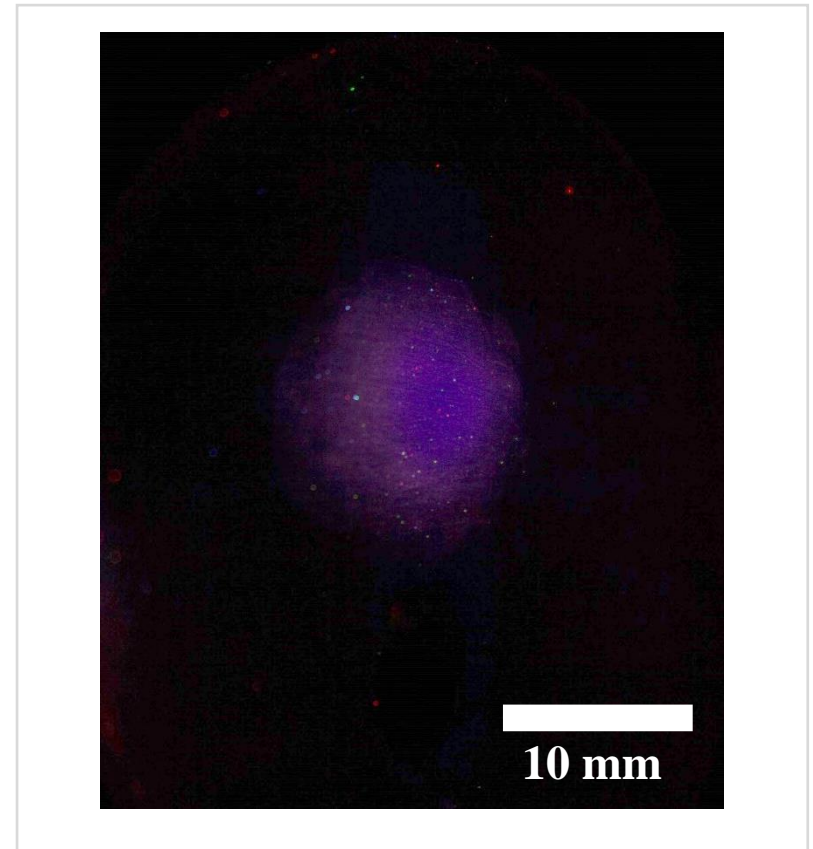
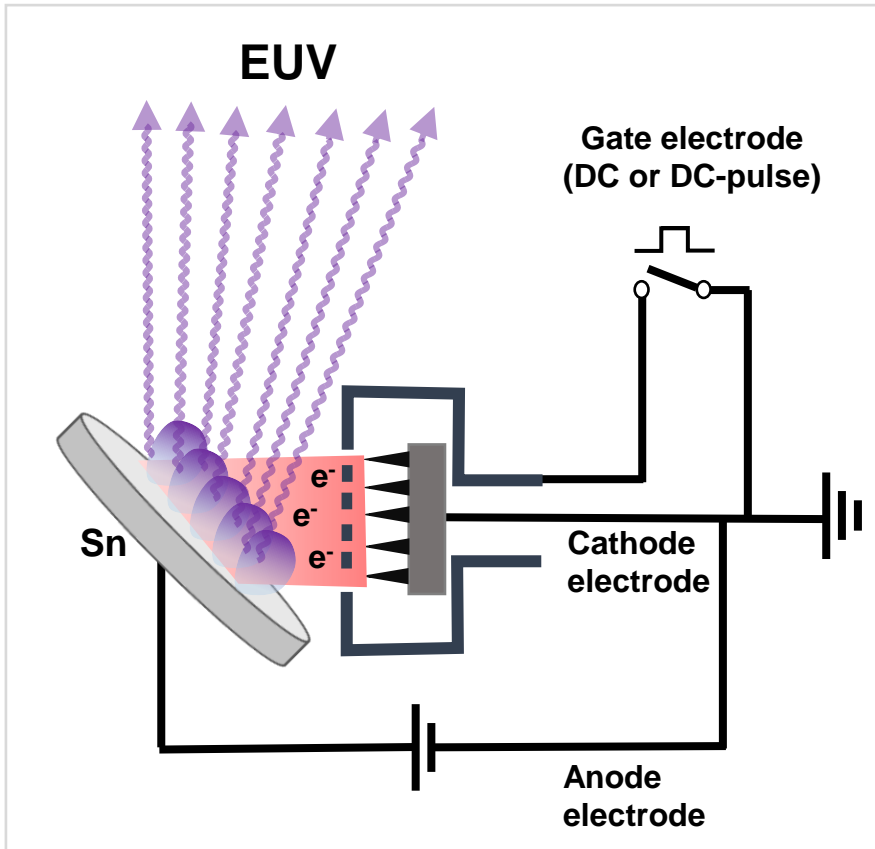
Laser produced plasma (LPP) source

- High power CO₂ laser
- **High-temperature plasma**
 - An average electron temperature of 76.6 eV
[Appl. Sci. 9, 2827 (2019)]
- Ultrahigh pulse driving (100 kHz)
- Very expensive



C-beam pumping technology

- Electron bombardment using C-beam
- **Cold plasma**
 - Less than 1 eV
[J. Appl. Phys. 110, 093304 (2011)]
- Multi-beam irradiation is possible
- Adjustable size of C-beam from micrometer to centimeter scale
- DC & DC-pulse power supply

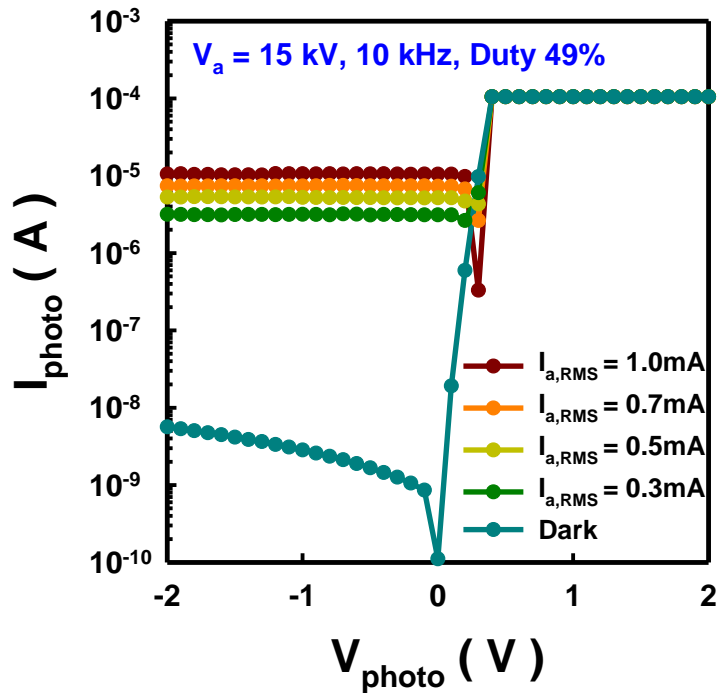


Schematic of EUV generation with C-beam

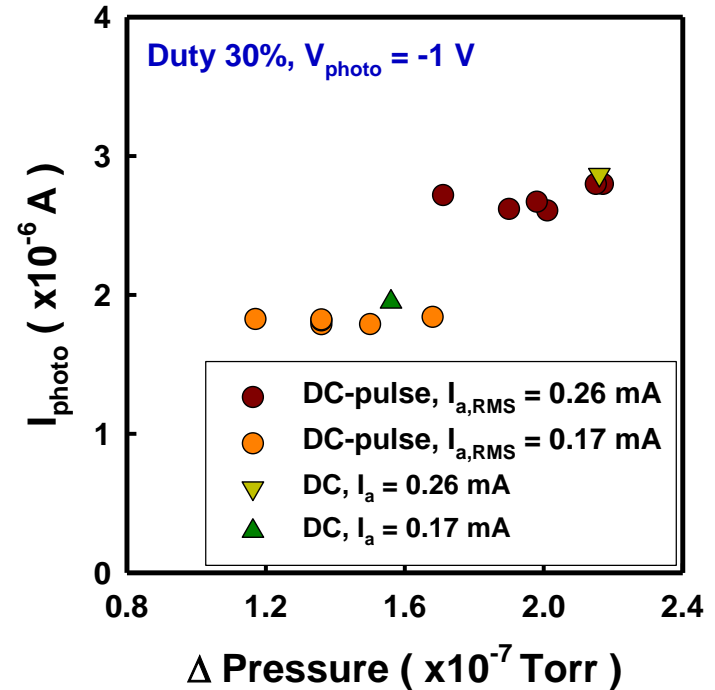
Photo of EUV-emitting plasma

- **Electrons emitted from the C-beam directly collide with Sn, excitation and ionization of Sn atoms evaporated by electron bombardment, resulting in EUV-emitting plasma.**

Controlling the intensity of EUV light



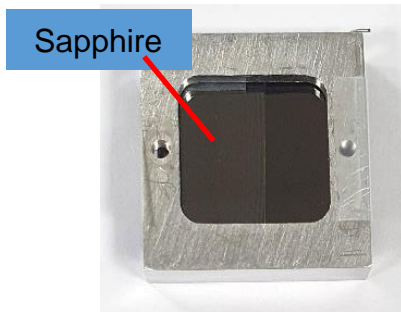
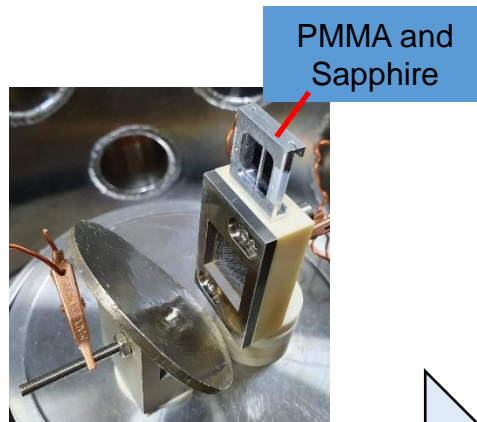
Photocurrent response



EUV intensity and Δ pressure with different driving

※ EUV photodiode equipped with a 150 nm thick Zr filter

- EUV intensity depends on C-beam parameters with anode impact power and driving.
- Unlike DC driving, DC-pulse driving generates EUV light with minimal pressure change by changing the frequency.



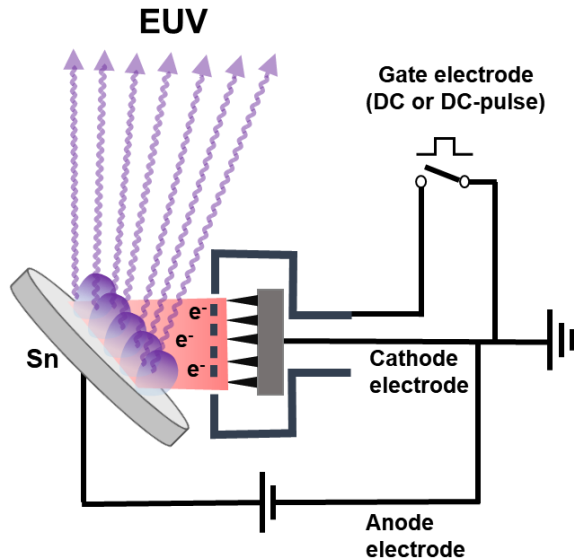
C-beam pumping

- V_a : 15 kV, 1 kHz, $I_{a,RMS}$: 0.4 mA
- Exposure time: 30 s



Optical microscope image after exposure and develop

- When observed with an optical microscope at 500 times magnification, the part covered by the sapphire and the part not covered by the sapphire can be accurately distinguished.



- EUV light generated by direct irradiation of C-beam was verified using a photodiode equipped with Zr filter and PMMA photoresist.
- EUV intensity depends on C-beam parameters with anode voltage, current, and DC-pulses.

References

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